

Reaction Pathway of Copper Atomic Layer Deposition via Time-of-Flight Mass Spectrometry

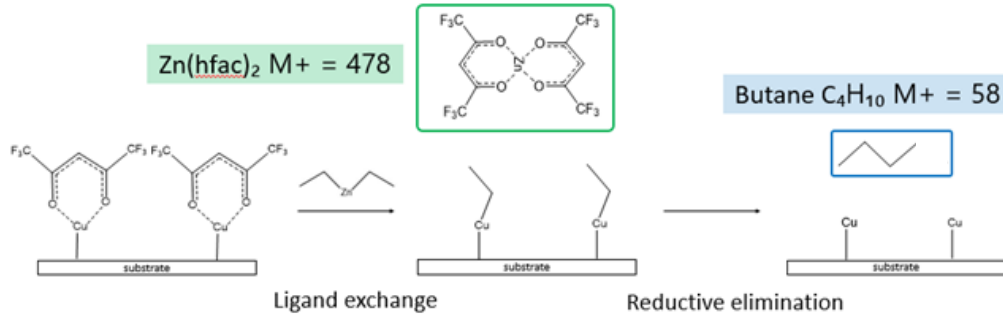


Fig.1: Hypothesized surface reaction mechanism between adsorbed Cu(hfac)₂ and DEZ.

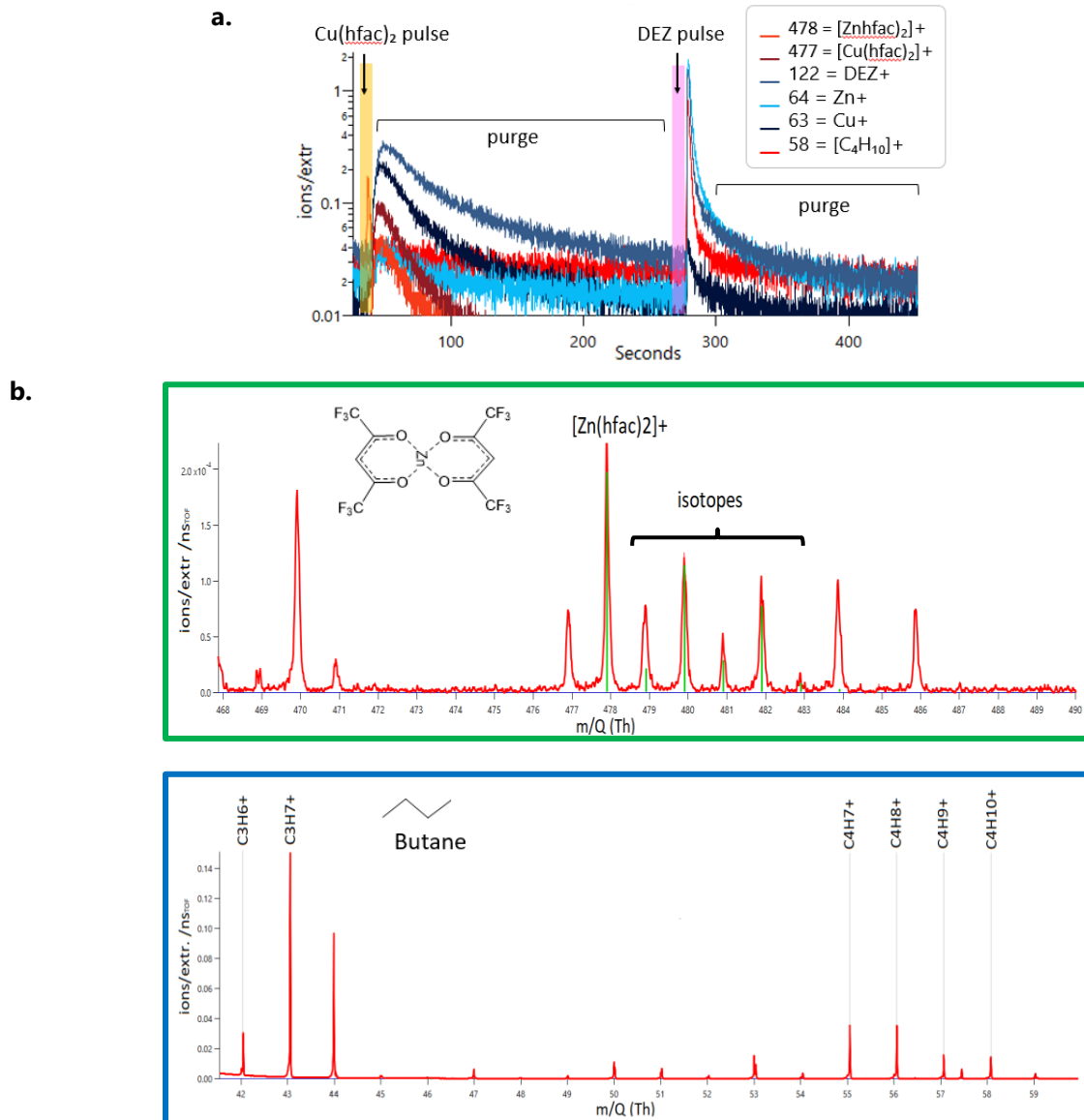


Fig.2: a. Time-resolved ToFMS monitoring during ALD cycle. **b.** Mass spectra during DEZ pulse.